

CENTURA 200mm DPS & 300mm DPSII PROCESS OVERVIEW

Who should attend?

This course is designed for those individuals in the semiconductor industry who require an overview of the Centura 200mm DPS or 300mm DPSII Etch Chambers process.

Course Benefits

Increase industry standard wafer process knowledge including fundamentals, analysis, and control.

Course Objectives

- Describe the basic concepts of the etch process.
- Identify the two primary RF coupling techniques used on chambers designed for etching etch poly and metal structures.
- Identify the hardware characteristics of the 200mm DPS poly and metal chambers.
- Identify the major components of the 300mm DPSII chamber.

Course Modules

1. Overview

Registration Information

Prerequisites: None

Course Length: 1 Hour

Course Type: Web-based Training

Course Number: TRNWEB-113

To enroll or for more information on our products and services, please call our registrar at one of the numbers below or go to www.appliedtraining.com.

- 1-800-468-8888, option 4 (United States)
- 1-512-272-0027 (International)

Computer System Requirements:

Attending this course requires a Windows 98, NT, 2000 or XP computer using Internet Explorer 5.5 or higher. 128MB RAM or higher and high-speed Internet access is also highly recommended.